

REMARKS

In accordance with the foregoing, the specification and claims 4, 7-8, and 19 have been amended. Claim 6 has been cancelled. Claims 4, 5 and 7-30 are pending and under consideration. Claims 1-3 are withdrawn from consideration.

The Specification and claims 7-8 have been amended to overcome the objections thereto.

The rejection based on Chen (U.S. '589) is now discussed. Independent claim 4 recites providing a single photo mask on the photo resist and exposing the photo resist to light by using the single photo mask. FIG. 9E of Chen illustrates the mask of this reference, which does not have a reference numeral. However, the mask is not on the cross-linking polymer, and thus is not on the photo resist, as claimed.

Claim 4 also recites "wherein the forming of the photo resist includes forming the photo resist to have a thickness from 35 μm to 100 μm ." It is respectfully submitted that Chen does not disclose this feature.

Accordingly, withdrawal of the rejection is requested.

There being no further outstanding objections or rejections, it is submitted that the application is in condition for allowance. An early action to that effect is courteously solicited.

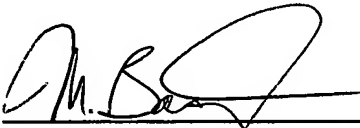
Finally, if there are any formal matters remaining after this response, the Examiner is requested to telephone the undersigned to attend to these matters.

If there are any additional fees associated with filing of this Amendment, please charge the same to our Deposit Account No. 19-3935.

Respectfully submitted,

STAAS & HALSEY LLP

Date: 6-10-05

By: 
Michael J. Badagliacca
Registration No. 39,099

1201 New York Avenue, NW, Suite 700
Washington, D.C. 20005
Telephone: (202) 434-1500
Facsimile: (202) 434-1501